



Docket No. 740756-2045

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:

Kenji ITOH et al.

Serial No. 09/412,510

Filed: October 5, 1999

For: PROCESS FOR TREATING A SUBSTRATE WITH
A PLASMA

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) Group Art Unit: 1762

) Examiner: Marianne Padgett

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) Date: March 17, 2003

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PRELIMINARY AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

Sir:

Please preliminarily amend the subject application as follows:

IN THE CLAIMS:

Please add new claims 73-86 as follows:

F1 ³² 73. (New) A process comprising the steps of:
providing first and electrodes opposed in parallel to each other in a reaction chamber,
said first electrode having a plurality of gas inlets arranged in a first direction;
introducing an etching gas through said plurality of gas inlets into said reaction
chamber;
generating a plasma of said etching gas by applying a voltage between said first and
second electrode wherein said plasma extends between the first electrode and the second
electrode and a cross section of the plasma along planes of the first and second electrodes has a
length along the first direction and a width along a second direction perpendicular to the first